# Single Event Effects characterization of a commercial 28 nm CMOS technology

## TWEPP 2023

2023/10/07 - Geremeas

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## EP-R&D - WP5.1



https://ep-dep.web.cern.ch/sites/ep-dep.web.cern.ch/files/Report%20final\_0.pdf



https://indico.cern.ch/event/1042567/contributions/4419842/attachments/2272167/3859068/PresentationIPBlocksForum V3\_noAdditionalSlides.pdf

## CERN & CMOS



#### data from:

 $https://www.tsmc.com/english/dedicatedFoundry/technology/logic/l_3nm https://irds.ieee.org/editions/2022/more-moore$ 

## ASICs in 28nm technology



list of Institutes that collaborate in 28nm-ASIC development projects with CERN

https://asic-support-docs.web.cern.ch//nda/

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## TID effects in 28nm technology

- investigation of TID effects in 28 nm technology is at an **advanced stage** AMs in a commercial 28
- Borghello, G., et al. "Total ionizing dose effects on ring-oscillators and SRAMs in a commercial 28 nm CMOS technology." *Journal of Instrumentation* 18.02 (2023): C02003.
- M. Piller *et al.*, "Generic Analog 8 Bit DAC IP Block in 28nm CMOS for the High Energy Physics Community," *2022 Austrochip Workshop on Microelectronics (Austrochip)*, Villach, Austria, 2022, pp. 5-8, doi: 10.1109/Austrochip56145.2022.9940783.
- Bonaldo, Stefano, et al. "Influence of halo implantations on the total ionizing dose response of 28-nm pMOSFETs irradiated to ultrahigh doses." *IEEE Transactions on Nuclear Science* 66.1 (2018): 82-90.
- Zhang, Chun-Min, et al. "Characterization and modeling of Gigarad-TID-induced drain leakage current of 28-nm bulk MOSFETs." *IEEE Transactions on Nuclear Science* 66.1 (2018): 38-47.
- Zhang, Chun-Min, et al. "Characterization of gigarad total ionizing dose and annealing effects on 28-nm bulk MOSFETs." IEEE Transactions on Nuclear Science 64.10 (2017): 2639-2647.

• ....

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#### What is the sensitivity to **Single Event Effects** (SEE) of **28nm** CMOS technology?





#### ANALOG IP BLOCKS



### chips received mid 2022

2023/10/05

## EXP28:SEE/ANA – TESTs

- Heavy-ions test at HIF (Louvain-La-Neuve, BE)
  - > 2 days of test end of November 2022

- Proton test at TRIUMF (Vancouver, CA) https://www.triumf.ca/pif-nif/proton-irradiation
  - 1 (long) day beginning of December 2022
    tested only EXP28-SEE

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Test system developed by Risto Pejašinović and Francisco Piernas Diaz!

### RADNEXT

## EXP28:SEE/ANA – TESTs

• Heavy-ions test at HIF (Louvain-La-Neuve, BE)

https://uclouvain.be/en/research-institutes/irmp/crc/heavy-ion-facility-hif.html

> 2 days of test end of November 2022

Proton test at TRIUMF (Vancouver, CA)

https://www.triumf.ca/pif-nif/proton-irradiation

1 (long) day beginning of December 2022
tested only EXP28-SEE

## RADNEXT

## EXP28:SEE/ANA – HI TEST

2 days of test in November 2022

## EXP28:SEE $\rightarrow$ tested for all ions at $\theta = 0^{\circ}$ and 45°

OCX	ail					
ionu	M/Q	lon	DUT energy [MeV]	Range [µm Si]	LET [MeV/(mg/cm²)]	E
	3.25	<sup>13</sup> C <sup>4+</sup>	131	269.3	1.3	
	3.14	<sup>22</sup> Ne <sup>7+</sup>	238	202.0	3.3	
	3.37	<sup>27</sup> Al <sup>8+</sup>	250	131.2	5.7	
	3.27	<sup>36</sup> Ar <sup>11+</sup>	353	114.0	9.9	
	3.31	<sup>53</sup> Cr <sup>16+</sup>	505	105.5	16.1	
	3.22	<sup>58</sup> Ni <sup>18+</sup>	582	100.5	20.4	
	3.35	<sup>84</sup> Kr <sup>25+</sup>	769	94.2	32.4	
	3.32	<sup>103</sup> Rh <sup>31+</sup>	957	87.3	46.1	
	3.54	<sup>124</sup> Xe <sup>35+</sup>	995	73.1	62.5	

https://uclouvain.be/en/research-institutes/irmp/crc/parameters-and-available-particles.html

EXP28:ANA

→ several combination of ion/angle/voltage (more details later)

 $\rightarrow$  fluence ~5x10<sup>6</sup> ni/cm<sup>2</sup> for each ion/angle



## RADNEXT

## EXP28:SEE/ANA – TESTs

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1 (long) day beginning of December 2022
 tested only EXP28-SEE



## RADNEXT

## EXP28:SEE/ANA – PROTON TEST

#### 1 (long) day beginning of December 2022

test n.	1	2	3	4	5	6	7
chip	А	А	А	А	В	В	В
energy [MeV]	480	480	480	480	480	480	480
fluence [cm <sup>-2</sup> × 10 <sup>9</sup> ]	174	182	184	184	183	184	184
flux [cm <sup>-2</sup> ×10 <sup>6</sup> /s]	520	130	1300	1300	1300	1300	1300

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- 2 chips (A, B)
- 2 energies (480, 350 MeV)

test n.	8	9	10	11	12	13	14	15	16	17	18
chip	В	В	В	В	В	В	А	А	А	А	А
energy [MeV]	350	350	350	350	350	350	350	350	350	350	350
fluence [cm <sup>-2</sup> ×10 <sup>9</sup> ]	90	183	183	184	184	90	184	184	64	385	385
flux [cm <sup>-2</sup> ×10 <sup>6</sup> /s]	256	256	640	640	640	128	640	640	128	640	640

## RADNEXT



first comprehensive overview of the SEE sensitivity of 28nm CMOS technology

- ✓ minimum distance between D-flip-flop to avoid MBU
- ✓ cross section of DFF for HI and protons
- ✓ cross section of foundry SRAMs for HI and protons
- ✓ MBU evaluation in scrambled SRAMs
- ✓ evaluation of a method to predict SEEs rate in the accelerator environment using heavy-ion data
- cross section and pulse length for SET with HI and protons
- ✓ multi-SET
- ✓ sensitivity to Single-Event-Latch-UP



#### first comprehensive overview of the SEE sensitivity of 28nm CMOS technology

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## • minimum distance between D-flip-flop to avoid MBU

- evaluation of a method to predict SEEs rate in the accelerator environment using heavy-ion data
- pulse length of SET for HI and protons
- sensitivity to **Single-Event-Latch-UP**

## **MULTI-BIT-UPSET**

#### Single-bit-upset (SBU)



#### Multi-bit-upset (MBU)





## TRIPLICATION

## **15 μm** typically used in **65nm** technology





Stefan Biereigel: Investigations on Multi-Bit Upsets in 65nm CMOS (https://indico.cern.ch/event/959655)

## What is the minimum distance between DFF to avoid MBU in **28nm** technology?

## EXP28:SEE

SINGLE EVENT EFFECT (SEE)

	CAPZO H
	SEE 🚦
2 mm	
	8
2 mm	
<u>Connenee</u> ee	

3 test structures:

• 7 matrices of D-flip-flops

• 4 foundry SRAMs

single- and multi-bit-upsets (SBU, MBU)

• 16 chains of inverters + vernier detector Single-event-transient (SET)

## EXP28:SEE

SINGLE EVENT EFFECT (SEE)

2 mm	Exp28 SEE
2 mm	

- 3 test structures:
- 7 matrices of D-flip-flops
- 4 foundry SRAMs

#### single- and multi-bit-upsets (SBU, MBU)

• 16 chains of inverters + vernier detector \_ single-event-transient

## EXP28:SEE – DFF







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## EXP28:SEE – DFF – MBU – protons





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## EXP28:SEE – DFF

**~6 μm spacing** between DFFs drastically reduces probability of MBU!

- key information for triplication strategy!
- ~2.5 times less than the 15 μm typically used in 65nm technology!



dimensions as drawn

2023/10/05

## EXP28:SEE – DFF – MBU

DFF

DFF

Т

A P T

A P

т

DFF

DFF

0

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F	DF	F
DFF <sup>A</sup>	DF	F

DFF	T A P	DFF
DFF	T A P	DFF
DFF	T A P	DFF

DFF	T A P	DFF
DFF	T A P	DFF

dimensions as drawn

## EXP28:SEE - DFF - MBU - HI

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 $^*$ 3.22  $\mu m$  for matrix 1



max MBU length = 2

DFF	T A P		T A P		∩ %
DFF	T A P	DFF	T A P	DFF	<b>U</b> /0 0/469

	T A P	
DFF	T A P	DFF



0/469



DFF	T A P	DFF
	T A P	DFF

0%

0/469

dimensions as drawn

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## EXP28:SEE – DFF – MBU – protons



\*3.22 μm for matrix 1



max MBU length = 2

DFF	T A P	DFF	T A P	DFF	
	T A P	DFF	T A P	DFF	0/57



## EXP28:SEE – DFF

**~6 μm spacing** between DFFs drastically reduces probability of MBU!

- key information for triplication strategy!
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dimensions as drawn





 evaluation of a method to predict SEEs rate in the accelerator environment using heavy-ion data

```
heavy-ions test:
```

- ☺ large statistic (many errors in a short amount of time)
- ☺ easier to trigger **single-event-latch-up** (SEL)

Inot representative of the radiation environment in particle detectors

## EXP28:SEE – DFF – $\sigma$ – protons



## EXP28:SEE

SINGLE EVENT EFFECT (SEE)

	Fyp20
2 mm	SEE
∠ mm	Ţ

3 test structures:

• 7 matrices of D-flip-flops

• 4 foundry SRAMs

#### single- and multi-bit-upsets (SBU, MBU)

• 16 chains of inverters + vernier detector (SFT)

## EXP28:SEE – SRAM



- 6 4096x32b single-port
- 14 2048x32b single-port UHD
- **4** 4096x32b dual-port
- 6 4096x32b dual-port UHD

Total active area: 0.76 mm<sup>2</sup>

## EXP28:SEE – SRAM – $\sigma$ – protons






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- minimum distance between D-flip-flop to avoid MBU
- evaluation of a method to predict SEEs rate in the accelerator environment using heavy-ion data
- pulse length of SET for HI and protons
- sensitivity to **Single-Event-Latch-UP**

## EXP28:SEE

SINGLE EVENT EFFECT (SEE)

	Exp28
	SEE -
2 mm	
2	
2 mm	
<u>Concessos</u>	

### 3 test structures:

• 7 matrices of D-flip-flops

• 4 foundry SRAMs

single- and multi-bit-upsets (SBU, MBU)

• 16 chains of inverters + vernier detector Single-event-transient (SET)

## EXP28:SEE – SET

#### VERNIER DELAY LINE TEST STRUCTURE :

Measure cross-section for transient

Estimate transient length vs let

Detect multiple-transient

Fully digital implementation

Fast readout through differential lines

Sensitive area ~400 x 80 um2 with minimum size inverters



M. Glorieux et al., "Detailed SET Measurement and Characterization of a 65 nm Bulk Technology," in IEEE Transactions on Nuclear Science, vol. 64, no. 1, pp. 81-88, Jan. 2017, doi: 10.1109/TNS.2016.2637935. P. Huang et Al, "Heavy-Ion-Induced Charge Sharing Measurement With a Novel Uniform Vertical Inverter Chains (UniVIC) SEMT Test Structure," in IEEE Transactions on Nuclear Science, vol. 62, no. 6, pp. 3330-3338, Dec. 2015







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- sensitivity to Single-Event-Latch-UP



## Single-Event Latch-UP (SEL)



## SEL test structure

Letch-up sensitivity depends on doping levels (which cannot be changed) and **distance between wells** 



**40** structures with different combinations of  $X_{NWPS}$ ,  $X_{SS}$ ,  $X_{PWNS}$ 

## EXP28:ANA – HI

ion	angle [°]	LET [MeV/(mg/cm <sup>2</sup> )]	fluence [10 <sup>6</sup> ni/cm <sup>2</sup> ]	voltage
Ni	0	20.4	23.3	VDD (0.9 V)
Ni	45	28.85	16.2	VDD
Kr	45	45.82	11.4	VDD
Хе	0	62.5	51.6	VDD
Rh	45	65.2	11.4	VDD
Хе	45	88.39	6.2	VDD
Хе	45	88.39	45.0	1.15*VDD
Хе	75	241.48	1.72	1.15*VDD
	high LET, high voltage			

## SEL test structure

Letch-up sensitivity depends on doping levels (which cannot be changed) and distance between wells



40 structures with different combinations of  $X_{NWPS}$ ,  $X_{SS}$ ,  $X_{PWNS}$ 

No SEL in any of the structures for any for the tests!!!

## CONCLUSIONS

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### first comprehensive overview of the SEE sensitivity of 28nm CMOS technology

- $\checkmark~5~\mu m$  distance to avoid MBU in DFF
- ✓ validation of model to estimate of proton cross section from HI tests
- ✓ SET pulse length for heavy-ions and protons

### ✓ no SEL for any structure/LET

- + cross section of DFF and 4 foundry SRAMs for HI and protons
- + MBU probability of DFF and 4 foundry SRAMs for HI and protons
- + MBU evaluation of scrambled SRAM
- + cross section for SET with HI and protons
- + multi SET

## EXTRA SLIDES

## **EXP28 CHIPS SUITE**

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SINGLE EVENT EFFECT (SEE)



ANALOG IP BLOCKS



chips received mid 2022

Goal:

- experience the design flow
- characterize the 28nm CMOS technology

   performance and radiation response



## HI vs PROTONS



sensitive area (where cells are located) p interacts with material (Si and/or metal) ->HI generated isotropically



### EXP28 SEU: SINGLE EVENT UPSET ON SEQUENTIAL ELEMENTS



Test structure derived from a multi-bit upsets test structure in 65nm (Stefan Biereigel, https://indico.cern.ch/event/959655)

- 7 matrices of 4096 DFF continuously clocked, D tied to Q.
- 9 tracks, different flavors.



Rad-Hard data processing and readout.

- 1 input line for clock (640MHz).
- 1 output line for data (16-bits packet at 640MHz).
- SEU detected readout FF reset.
- In case of MSEU, an arbiter ensures priority.

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## EXP28:SEE – DFF – cross section $(\sigma)$



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## $\mathsf{EXP28}:\!\mathsf{SEE}-\mathsf{SRAM}-\sigma-\mathsf{HI}$





# TWEPP 2023: Single Event Effects characterization of a commercial 28 nm CMOS technology **EXP28:SEE – SRAM – cross section – HI**



comparable or slightly better than 65nm





3 MBU/8 HITS = 37.5% : probability that a particle triggers an MBU ( $P_{MBU}$ )





MBU length increases with LET

similar to HI @ 5.7 MeV/(mg/cm<sup>2</sup>)



## $\mathsf{EXP28}:\mathsf{SEE}-\mathsf{DFF}-\sigma-\mathsf{HI}$

 $\rightarrow \text{Weibull fit} \longrightarrow \sigma = \sigma_0 \left( 1 - e^{-\left[\frac{LET - LET_0}{W_\sigma}\right]^s} \right)$ form HI to representative environment DFF - matrix 0 ( $f \simeq 5 \times 10^6 \,\mathrm{ions/cm^2}$ DFF - matrix 3 ( $f \simeq 5 \times 10^6 \text{ ions/cm}^2$ DFF - matrix 1 ( $f \simeq 5 \times 10^6 \text{ ions/cm}^2$ ) DFF - matrix 2 ( $f \simeq 5 \times 10^6 \text{ ions/cm}^2$ )  $10^{-1}$  $10^{-8}$  $10^{-1}$ 00 Δ  $^{-01}$   $\sigma_{\mathrm{DFF}}^{-10}$  [cm<sup>2</sup>] 10  $10^{-}$  $10^{\circ}$  $1 \ \sigma_{
m DFF} \ [
m cm^2]$  $1 \over \sigma_{
m DFF} \, [{
m cm}^2]$  $10^{-10}$   $\frac{10^{-10}}{10^{-10}}$ o  $\sigma_0 = 3.62 \mathrm{n}$  $\sigma_0 = 2.31 n$  $\sigma_0 = 3.47 \mathrm{n}$  $\sigma_0 = 3.72 n$  $LET_{0} = 20.0 \, \mathrm{p}$  $|LET_0 = 8.0p|$  $LET_{0} = 14.0p$  $LET_0 = 56.0 \mathrm{p}$  $W_{\sigma} = 21.97$  $W_{\sigma} = 21.97$  $W_{\sigma} = 21.97$  $W_{\sigma} = 21.97$ LET-LET01 LET-LET0 1  $\int LET - LET_0 1^s$  $LET - LET_0 1^s$  $\sigma = \sigma$  $\sigma = \sigma_0$ = 1.0= 1.0= 1.0 $10^{-1}$  $10^{-1}$  $10^{-11}$  $10^{-11}$ 102030 405060 102030 40 5060 10203040 5060 0 102030 405060 0 0 0  $\rm LET_{eff}\,[MeV/(mg/cm^2)]$  $LET_{eff} [MeV/(mg/cm^2)]$  $LET_{eff} [MeV/(mg/cm^2)]$  $LET_{eff} [MeV/(mg/cm^2)]$ Huhtinen, M., and F. Faccio. DFF - matrix 4 ( $f \simeq 5 \times 10^6 \,\mathrm{ions/cm^2}$ ) DFF - matrix 5 ( $f \simeq 5 \times 10^6 \,\mathrm{ions/cm^2}$ DFF - matrix 6 ( $f \simeq 5 \times 10^6 \,\mathrm{ions/cm^2}$ )  $10^{-}$  $10^{-}$  $10^{-8}$ Single Event Upset rates in an  $10^{-9}$  $^{-90}_{-10} \, {\rm Gm^2}_{-10}$  $^{-01}$   $\sigma_{\mathrm{DFF}}$  [cm<sup>2</sup>]  $\sigma_{\mathrm{OFF}}$  ]  $\sigma_{\rm DFF} \left[ {\rm cm^2} \right]$ 450.1 (2000): 155-172.  $\sigma_0 = 3.11$ n  $\sigma_0 = 3.81 n$  $\sigma_0 = 3.24 n$  $10^{-}$  $LET_0 = 283.0 \text{m}$  $LET_{0} = 38.0 \text{p}$  $LET_0 = 36.0 \text{p}$  $W_{\sigma} = 21.59$  $W_{\sigma} = 21.97$  $W_{\sigma} = 21.97$ LET-LET0 [LET-LET0] [LET-LET0]  $\sigma = \sigma_0$ = 1.0 $\sigma = \sigma_0$  $\sigma = \sigma_0$ = 1.0s = 1.0 $10^{-12}$  $10^{-11}$  $10^{-11}$ 0 102030405060 0 102030405060 0 102030405060  $m LET_{eff} [MeV/(mg/cm^2)]$  $LET_{eff} [MeV/(mg/cm^2)]$  $LET_{eff} [MeV/(mg/cm^2)]$ 



## EXP28:SEE – SRAMs (HI)



### ~ independent of bit value

## EXP28:SEE – SRAM – MBU



somewhere else

#### scrambled address:

32-world bits scrambled around the SRAM

bits of the same world physically separated

 $\mathbf{\nabla}$ 

# in the SRAM another bit b1/w0 b1/w1 b1/w2 b1/w3 b1/w4 b1/w5 b1/w6 b1/w7

difficult to have multi-bits-upset on the same word

## EXP28:SEE – SRAM – MBU

#### same bit/different words

b0/w0	<b>b0/</b> w1	b0/w2	b0/w3	
b0/w4	<mark>b0/</mark> w5	<mark>b0/w6</mark>	<mark>b0/</mark> w7	

#### different bits/different words

	<mark>b0/</mark> w0	b0/w1	<mark>b0/</mark> w2	<mark>b0/w3</mark>
$\langle \neg \rangle$	<mark>b0/</mark> w4	<mark>b0/</mark> w5	<mark>b0/</mark> w6	<mark>b0/</mark> w7
	bN/w8	<b>bN/</b> w9	bN/w10	<b>bN/</b> w11

different bits/same word



MBU type B

## EXP28:SEE - SRAM - MBU - HI



same bit/different words				
	<mark>b0/</mark> w0	<b>b0/</b> w1	<mark>b0/</mark> w2	b0/w3
	b0/w4	<mark>b0/</mark> w5	<mark>b0/w6</mark>	b0/w7

#### different bits/same word

<mark>b0/</mark> w0	<b>b0/</b> w1	<mark>b0/</mark> w2	<mark>b0/w3</mark>
<mark>b0/</mark> w4	<mark>b0/</mark> w5	<mark>b0/w6</mark>	<mark>b0/</mark> w7



...





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different bits/different words

**b0/**w2

b0/w6

bN/w10

b0/w3

b0/w7

b**N/**w11

**b0/**w1

b0/w5

bN/\

**b0/**w0

**b0/**w4

bN/w8

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## EXP28:SEE – SRAM – MBU – protons





### EXP28 SEE: SINGLE EVENT TRANSIENT

#### Simulation results



Requires process calibration with Ring-Oscillator Transient length range up to 1 ns (typical) Transient minimum detection ~ 25 ps (typical)

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2023/10/05



## EXP28:SEE - SET - HI





## EXP28:SEE – SET (HI)

### Multi-SET only of high LET




## RD53<sup>\*</sup>: triplicated clock tree with skew for SET filtering

 $https://indico.cern.ch/event/1038992/contributions/4363708/attachments/2256379/3829070/LHCC_RD53\_June2021.pdf$ 

\*readout chips for the ATLAS and CMS pixel detector (https://rd53.web.cern.ch/)

## recently measured in chips for ALICE and LHCb! (130nm CMOS technology)

\_\_\_\_\_

[1] Mahmood S.M., Roeed K., ALICE Collaboration Collaboration, "Investigation of single event latch-up effects in the ALICE SAMPA ASIC", PoS, TWEPP2018 (2019), p. 023 5 p, 10.22323/1.343.0023, URL https://cds.cern.ch/record/2710375

- [2] Lemos Cid E., Vázquez Regueiro P., "The VeloPix ASIC test results", PoS, Vertex 2017 (2018), p. 052, 10.22323/1.309.0052
- [3] Faccio, Federico. "ASIC survival in the radiation environment of the LHC experiments: 30 years of struggle and still tantalizing." NIMA (2023)

## EXP28 ANA: GENERAL DESIGN GUIDELINE

## SINGLE EVENT LATCHUP:

EVALUATE MINIMUM DISTANCE BETWEEN SUBSTRATE CONTACTS

REQUIRES PER CELL POWER MEASUREMENT

RE-USE POWER GATING CELL FROM RING-OSCILLATOR

WITH AND WITHOUT DEEP N-WELL







Annotated diagram of the PNPN SEL test structure showing terminal names, terminal values, and linear dimensions

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heavy ions and proton test: end of 2022/beginning of 2023

beam time obtained through RADNEXT (for free)



https://radnext.web.cern.ch/